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Notice of Allowability	Application No.	Applicant(s)		
	10/730,234	BEINTNER ET AL.		
	Examiner	Art Unit		
	Mahmoud Dahimene	1765		
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this app or other appropriate communication GHTS. This application is subject to	olication. If not include will be mailed in due	ed course. THIS	
1. This communication is responsive to 12/09/2003.				
2. 🔀 The allowed claim(s) is/are <u>1-26</u> .				
<ol> <li>Acknowledgment is made of a claim for foreign priority una)</li></ol>	been received.  been received in Application No cuments have been received in this communication to file a reply	national stage applica		
4. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give	itted. Note the attached EXAMINER' es reason(s) why the oath or declara	S AMENDMENT or Nation is deficient.	IOTICE OF	
<ul> <li>CORRECTED DRAWINGS ( as "replacement sheets") mus (a)  including changes required by the Notice of Draftspers         <ul> <li>(a)  including changes required by the Notice of Draftspers</li> <li>(b)  including changes required by the attached Examiner's Paper No./Mail Date</li> </ul> </li> <li>Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in the deponsion of the deponsion of</li></ul>	son's Patent Drawing Review (PTO- s Amendment / Comment or in the C .84(c)) should be written on the drawing the header according to 37 CFR 1.121(c sit of BIOLOGICAL MATERIAL r	office action of new the graph of the distribution of the graph of the		
Attachment(s)	5. □ Notice of Informal P	atent Application (PT	O-152\	
<ol> <li>Notice of References Cited (PTO-892)</li> <li>Dotice of Draftperson's Patent Drawing Review (PTO-948)</li> </ol>	<del>-</del>	<ul> <li>5. Notice of Informal Patent Application (PTO-152)</li> <li>6. Interview Summary (PTO-413),         Paper No./Mail Date</li> <li>7. Examiner's Amendment/Comment</li> <li>8. Examiner's Statement of Reasons for Allowance</li> </ul>		
3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0	_ Paper No./Mail Dat			
Paper No./Mail Date  4. Examiner's Comment Regarding Requirement for Deposit of Biological Material				
		9. Other		
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## Allowable Subject Matter

Claims 1-26 allowed.

The following is an examiner's statement of reasons for allowance:

Regarding claims 1 and 19, the cited prior art of record fails to disclose a method of forming at least on fin extending from a substrate comprising the step of removing said first hardmask, leaving at least one etch aperture in said second mask having a width equal to a fin separation distance between adjacent fins, in combination with the rest of the limitations of claim 1 and 19.

Similarly, regarding claim 10, the cited prior art of record fails to disclose a method of forming a set of fins extending from a substrate comprising the step of expanding the transverse dimension of said at least one aperture in said first hardmask relative to the transverse dimension of said at least one aperture in said fin layer by removing a portion of said first hardmask above each of said two fin blocks, thereby exposing a corresponding portion of each of said two fin blocks with a predetermined width, in combination with the rest of the limitations in claim 10.

The closest art found include the following references:

Yu (US 6391782) discloses a method for forming sub-lithographic fins using a spacer material (48) deposited on the fin block, this method makes use of a self-aligned process, but no second mask is used. Doris et al. (US 20040266076) discloses a

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second mask (30) and pull-back the hard-mask on one set of fins (32) while the other set is covered (34) by the second mask, but no structure is defined by differential etching as claimed by the applicant. Other hard-mask pull-back methods are disclosed, such as Isobe (US 6417047) who also uses a second mask, but no features are obtained such as the ones claimed by the applicant.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Mahmoud Dahimene whose telephone number is (571) 272-2410. The examiner can normally be reached on week days from 8:00 AM. to 5:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on (571) 272-1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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MD

SUPERVISORY PATENT EXAMPLER